

IS1000 ION SOURCE

Dynavac's Model IS1000 Ion/Plasma Source is the right choice for Ion Assisted Deposition (IAD) of full-density coatings and for ion cleaning of substrates before deposition. It has a high beam power capability operating at energy levels from 150 to 600eV. Operation of the source at low energy levels produces films with minimum absorption. A broad beam with an enhanced angle of approximately 60° allows coverage of large substrate areas with high deposition rates. The IS1000 is easy to maintain and capable of operating with oxygen and other gases on a continuous basis. It uses a simple and easily changed tungsten filament to supply electrons for charge neutralization.



Specifications

- Source diameter: 6.25"
- Height: 6.25"
- Aperture: 3"
- Weight: 12 lbs
Stationary or gimbal mounted

Gas/Neutralizer Control and Power Supply System

- Dual gas operation
- Dimensions: 7"H x 19"W x 20.5"D
- Neutralizer: 18" x .020 tungsten wire
- Weight: 40 lbs

High Voltage Power Supply

- Advanced Energy MDX-5
- Load Power: 5000 W
- Line Power: 208 ±10% VAC, 3Ø, 20A
- Output Maximum: 0-640VDC, 10A
- Dimensions: 7"H x 19"W x 19"D
- Weight: 75 lbs

Operational

- Drive Power: 0-1200 W
- Drive Energy: 150-600 eV
- Drive Current: .5 - 7A
- Cone Angle: 60 degrees
- Minimum pumping: 10,000 l/s

Gas and Water Feedthroughs

- 1" diameter or Conflat

Utilities

- Power: 208V, 1Ø, 5.3A, 50-60Hz
- Water: 1-2 gpm
- Gas: 50 sccm maximum